Claims:

1. A method for tuning a plasma in a chamber, the method comprises:

providing a first radio frequency power to a first electrode embedded in a substrate support assembly, the substrate support assembly positioned adjacent to a showerhead in the chamber;

providing a second radio frequency power to a second electrode embedded in the substrate support assembly at a location different than the first electrode, wherein the second electrode circumferentially surrounds the first electrode;

monitoring parameters of the first and second radio frequency power; and

tuning the plasma based on the monitored parameters,

wherein the tuning comprises tuning one or both of the first electrode and the second electrode when one or both of the first and second electrode is a source of radio frequency power, and wherein the showerhead is electrically grounded.